

449 MODIFIED

Docket No.: 2950.54US01 Application No.: 10/027,906

INFORMATION DISCLOSURE CITATION IN AN APPLICATION

APPLICANT: BI et al.

FILING DATE: December 21, 2001

**GROUP ART UNIT: 3662** 

EXAMINER	DOCUMENT	<del></del>	J.S. PATENT DOCUM	22.110	T	FILING DATE IF
INITIAL	NO.	DATE	NAME	CLASS	SUBCLASS	APPROPRIATE
MAO	3,806,570	04/1974	Flamenbaum et al.	_	1	
	3,883,336	05/1975	Randall			-
	3,923,484	12/1975	Randall			_
	3,932,162	01/1976	Blankenship			-
	3,934,061	01/1976	Keck et al.			
	4,038,370	07/1977	Tokimoto et al.		_	
	4,113,844	09/1978	Tokimoto et al.			-
	4,619,680	10/1986	Nourshargh et al.	_	-	
	4,735,677	04/1988	Kawachi et al.	)	_RE(	EIVED
	4,791,648	12/1988	Vojak et al.		- 00	
	4,814,289	03/1989	Baeuerle		061	2 9 2002
	4,868,005	09/1989	Ehrlich et al.		GDO	115
	4,881,791	11/1989	Mallinson et al.		-Sino	UP 3600
	4,933,262	06/1990	Beguin			
	5,060,595	10/1991	Ziv et al.		<b>—</b>	
	5,108,952	04/1992	Matsuhashi			
	5,119,460	06/1992	Bruce et al.			,
	5,141,549	08/1992	Tumminelli			
	5,195,161	03/1993	Adar et al.		-	
	5,200,029	04/1993	Bruce et al.	_		
	5,276,012	01/1994	Ushida et al.			
	5,296,072	03/1994	Dannoux et al.	.—		_
	5,317,576	05/1994	Leonberger et al.		_	
_	5,318,614	06/1994	Beguin			-
	5,385,594	01/1995	Kanamori et al.			
	5,396,507	03/1995	Kaminow et al.			
	5,447,585	09/1995	Dannoux et al			
	5,448,586	09/1995	Shmulovich et al.	~		
1	5,551,966	09/1996	Hirose et al.	~		
MD	5,556,442	09/1996	Kanamori et al.			
<del>-   \                                  </del>						

EXAMINER SIGNATURE

Mark le Ner

DATE CONSIDERED

9/22/2004

EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to the applicant.



FORM POOR MODIFIED

Docket No.: 2950.54US01 Application No.: 10/027,906

## INFORMATION DISCLOSURE CITATION IN AN APPLICATION

APPLICANT: BI et al.

FILING DATE: December 21, 2001 COOLID A DT LINIT: 3662

GROUP ART UNIT: 3662						
		U.S	. PATENT DOCL	<b>IMENTS</b>		
EXAMINER INITIAL	DOCUMENT NO.	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
INITIAL	5,622,750	04/1997	Kilian et al.			
	5,666,372	09/1997	Ball et al.		<u> </u>	<u> </u>
	5,729,642	03/1998	Thaniyavarn			
	5,790,730	09/1998	Kravitz et al.			
	5,863,604	01/1999	Hunt et al.			
	5,870,417	02/1999	Verdiell et al.			
	5,874,134	02/1999	Rao et al.			
	5,885,904	03/1999	Mehta et al.			
	5,930,439	07/1999	Ojha et al.			
	5,958,348	09/1999	Bi et al.			
	5,966,478	10/1999	Marcuse et al.			
	5,997,956	12/1999	Hunt et al.			
	6,011,981	01/2000	Alvarez et al			
	6,032,871	03/2000	Börner et al.			
	6,074,888	06/2000	Tran et al.			
	6,097,144	08/2000	Lehman			
	6,137,933	10/2000	Hunter et al.			
	6,160,830	12/2000	Kiely et al.			
	6,177,290	01/2001	Jang et al.			
	6,193,936	02/2001	Gardner et al.			
	6,227,722	05/2001	Kropp			
	6,254,928	07/2001	Doan			
	6,256,442	07/2001	Nolan et al.			
	6,280,802	08/2001	Akedo et al.			
	6,289,032	09/2001	Fay et al.		<u> </u>	ECE
	6,293,688	09/2001	Deacon			ECEIVE
-mad	6,307,995	10/2001	Veligdan			OCT 2 9 2002
					G <sub>P</sub>	2002
					9,1	OUP 360
						. 200
					<u> </u>	
	R SIGNATUI	Helln	er	DATE C	ONSIDERED 22/2004	

EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to the applicant.



FORM PROPERTY MODIFIED

Docket No.:
2950.54US01

Application No.:
2950.54US01

APPLICANT: BI et al.
FILING DATE: December 21, 2001

IN AN APPLICATION **GROUP ART UNIT: 3662** FOREIGN PATENT DOCUMENTS **EXAMINER** DOCUMENT NO. TRANSLATION SUBCLASS NO COUNTRY **CLASS** YES INITIAL DATE OVAP 05/1999 **PCT** WO 99/23189 PCT WO 99/31532 06/1999 PCT 12/1999 WO 99/61244 **PCT** Abstract WO 00/24093 04/2000 only 02/2001 **PCT** WO 01/07155 WO 01/22542 03/2001 **PCT** WO 01/77732 10/2001 **PCT** WO 02/32588 04/2002 **PCT PCT** WO 02/44765 06/2002 OTHER DOCUMENTS (including Author, Title, Date, Pertinent Pages, etc.) Rabii et al., "Recent advances in the fabrication of hollow glass waveguides", SPIE Vol. MAD 3262, pp. 103-107, 1998. Liang et al., "Laser synthesize silicon-based and ferro-based nano powders", SPIE Vol. 3862, pp. 17-21, 1999. Barbarossa et al., "Effect of temperature gradient on sintering kinetics of doped silica waveguides by flame hydrolysis deposition", SPIE Vol. 1794 Integrated Optical Circuits II, pp. 191-197, 1992. Lebedev et al., "Laser distillation-deposition synthesis of silica glasses with variable concentrations of oxygen deficient centers", SPIE Vol. 2498, pp. 65-71, 1995. Barbarossa et al., "High-silica cascaded three-waveguide couplers for wideband filtering by Flam Hydrolysis on Si", SPIE Vol. 1583 Integrated Optical Circuits, pp. 122-128, 1991. Barbarossa et al., "Optical damage threshold of P2O5 and GeO2-P2O5-doped silica waveguides", SPIE Vol. 1794 Integrated Optical Circuits II, pp. 185-190, 1992. Barbarossa et al., "High-silica low-loss three waveguide couplers on Si by Flame Hydrolysis Deposition", SPIE Vol. 1513 Glasses for Optoelectronics II, pp. 37-43, 1991. Maxwell, "Photosensitivity & rare-earth doping in flame hydrolysis deposited planar silica waveguides", SPIE Vol. 2695, pp. 16-29, 1996. Sun et al., "Building passive components with silica waveguides", SPIE Vol. 3795, pp. 313-319, 1999.

EXAMINER SIGNATURE Hellner DATE CONSIDERED 9/22/2004

EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to the applicant.



FORM P	DIFIED	Docket No.: 2950.54US01	Application No.: 10/027,906						
INFODA	MATION DISCLOSURE CITATION	APPLICANT: BI et al.							
INFORM	IN AN APPLICATION	FILING DATE: December 21, 2001							
		GROUP ART UNIT: 3662							
	OTHER DO	CUMENTS							
Examiner Initials	(Author, Title,	Date, Pertinent Pages, etc.)							
0.00	Center for Nano Particle Control, Website Mansoo CHOI, Associate Professor of								
1/1/10	Mechanized Engineering, Seoul National University, June 2000.								
	Saini et al., "Passive Active Resonant Coupler (PARC) Platform with Tapered Passive Waveguide", Proceedings of SPIE, Vol. 4087, pp. 254-255, 2000.								
	Teloptics Corp. Technology Overview, Website Teloptics, 3 pages, 2001.								
	Bryan, "Layer Materials and Planar Optical Devices", U.S. Patent Application No. 09/931,977, filed August 17, 2001, 62 pages.								
	Bryan, "Reactive Deposition for the Formation of Chip Capacitors", U.S. Provisional								
	Application No. 60/312,234, filed Augu	st 14, 2001, 42 pages.							
anarl	Horne et al., "Doped Glass Materials", U.S. Provisional Application No. 60/313,588,								
-V VIO	filed August 17, 2001, 35 pages.		,						
		_							
	RECEIVED  OCT 2 9 2002  GDOLL								
	OCT 2 9 2002								
	GROUD								
	GROUP 3600								
			·						
•									
EXAMIN	ER . 1 11 11 -	DATE 0 /2	21-11						
SIGNATU	TRE Mark Hellner	00:10 <u>10</u> 1010	2/2004						
EXAMINER not in confor	: Initial if citation considered, whether or not citation i mance and not considered. Include copy of this form w	s in conformance with MPEP § 609 with next communication to the application to the appli	<ol> <li>Draw line through citation if licant.</li> </ol>						